

Title (en)
OPTICAL CHARACTERISTIC MEASURING DEVICE, OPTICAL CHARACTERISTIC MEASURING METHOD, EXPOSURE DEVICE, EXPOSURE METHOD, AND DEVICE MANUFACTURING METHOD

Title (de)
EINRICHTUNG UND VERFAHREN ZUR MESSUNG EINER OPTISCHEN KENNGRÖSSE, BELICHTUNGSEINRICHTUNG, BELICHTUNGS-VERFAHREN UND BAUELEMENTEHERSTELLUNGSVERFAHREN

Title (fr)
DISPOSITIF DE MESURE DES CARACTERISTIQUES OPTIQUES, METHODE DE MESURE DES CARACTERISTIQUES OPTIQUES, DISPOSITIF D'EXPOSITION, METHODE D'EXPOSITION, ET UNE METHODE POUR FABRIQUER LE DISPOSITIF

Publication
EP 1796142 A4 20101006 (EN)

Application
EP 05770442 A 20050809

Priority
• JP 2005014585 W 20050809
• JP 2004232370 A 20040809

Abstract (en)
[origin: EP1796142A1] An optical property measurement apparatus (90) is equipped with an optical system unit (93) that selectively places an opening section (97) for passing illumination light, a microlens array (98) for measuring wavefront aberration, and a polarization detection system (99) for measuring a polarization state of the illumination light on an optical path of the illumination light. Accordingly an illumination shape and a size of an illumination optical system, wavefront aberration of a projection optical system and a polarization state of the illumination light can be measured together. Therefore, for example, even when exposure is performed with polarized illumination that is a type of modified illumination, highly-accurate exposure can be achieved by adjusting various optical systems based on the measurement results.

IPC 8 full level
H01L 21/027 (2006.01); **G01M 11/02** (2006.01); **G03F 7/20** (2006.01)

CPC (source: EP KR US)
G03F 7/70133 (2013.01 - EP KR US); **G03F 7/70141** (2013.01 - EP KR US); **G03F 7/70258** (2013.01 - EP KR US); **G03F 7/70566** (2013.01 - EP KR US); **G03F 7/706** (2013.01 - EP KR US); **G03F 7/7085** (2013.01 - EP KR US)

Citation (search report)
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• [XAY] JP 2004163313 A 20040610 - NIKON CORP
• [YA] US 2004114150 A1 20040617 - WEGMANN ULRICH [DE], et al
• [XA] JP 2002372406 A 20021226 - NIKON CORP
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• [E] EP 1670043 A2 20060614 - NIKON CORP [JP]
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